## **AMENDMENTS TO THE CLAIMS**

Please AMEND claims 28 and 30 as shown below.

The following is a complete list of all claims in this application.

1-27. (Cancelled)

28. (Currently Amended) A thin film transistor array panel, comprising:

a plurality of pixels defined by gate lines and data lines; and

a plurality of thin film transistors and pixel electrodes formed at the pixel and electrically

connected to the gate lines and the data lines,

wherein a semiconductor layers of the thin film transistors have a semiconductor layer

and an ohmic layer, said semiconductor layer having a double-layered structure with a lower

layer and an upper layer including made of amorphous silicon layers, which have different, band

gaps.

29. (Currently Amended) The thin film transistor array panel of claim 28, wherein the

semiconductor layers include a first amorphous silicon layer and a second upper amorphous

silicon layer is formed on the first-lower amorphous silicon layer, wherein the band gap of the

second-upper amorphous silicon layer is lower-less than that of the first-lower amorphous silicon

layer.

30. (Currently Amended) A thin film transistor array panel, comprising:

a plurality of pixels defined by gate lines and data lines; and

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a plurality of thin film transistors and pixel electrodes formed at the pixel and electrically connected to the gate lines and the data lines,

wherein a-thin film transistors have a gate insulating layer that is one element of the thin film transistor, said gate insulating layer-havinge a double-layered structure including a lower insulating layer and an upper insulating layer, wherein one of the insulating layers is composed of an organic insulating material, and the other is composed of at least one of amorphous silicon nitride and amorphous silicon oxide.

31-35 (Cancelled)